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Claims

1. A column line structure for use in a cathode assembly of an FED, comprising:
a conductive structure;
10 a resistive layer formed on said conductive structure; and
an insulative layer formed partly over said resistive layer.
2. The column line structure of Claim 1 wherein said conductive structure comprises
metal.
3. The column line structure of Claim 1 wherein said conductive structure comprises
15 aluminum.
4. The column line structure of Claim 1 wherein said resistive layer comprises
silicon.
5. The column line structure of Claim 1 wherein said insulative layer comprises
silicon oxide.
- 20 6. 5. The column line structure of Claim 1 wherein said insulative layer
comprises silicon nitride.
7. The column line structure of Claim 1 wherein said insulative layer comprises a
strip having a thickness of about 1000 Å.
8. An FED, comprising a cathode assembly and an anode assembly assembled with
25 said cathode assembly, wherein said cathode assembly includes an addressing matrix comprising
multiple row lines and column lines, said column lines having an insulation layer thereon to
inhibit shorting with the row lines.